

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		09/720,761	LAERMER ET AL.	
		Examiner	Art Unit	Page 1 of 1
		Kin-Chan Chen	1765	

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,302,536	04-1994	Josquin, Wilhelmus J. M. J.	438/595
	B	US-5,389,570	02-1995	Shiozawa, Junichi	438/243
	C	US-5,861,343	01-1999	Tseng, Horng-Huei	438/666
	D	US-5,182,234	01-1993	Meyer, Theodore O.	438/695
	E	US-5,047,115	09-1991	Charlet et al.	216/64
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages			
	U	Flamm, D. et al. "Multiple-Etchant Loading Effects and Silicon Etching in ClF3 and Related Mixtures", Journal of The Electrochemical Society, Dec. 1982, USA, Bd.129, Nr.12, pp.2755-2760.			
	V				
	W				
	X				

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.